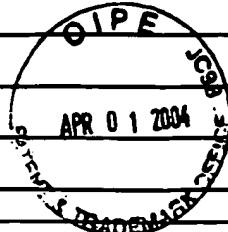


INFORMATION DISCLOSURE CITATION

Atty. Docket No. 04329.2802-01000	Appn. No. 10/698,456
Applicant Mari INOUE	
Filing Date November 3, 2003	Group: To be Assigned



U.S. PATENT DOCUMENTS

Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate

FOREIGN PATENT DOCUMENTS

	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No
	Japanese Patent Application KOKAI Publication No. 2000-20564	01/21/2000	Japan			NO
	Korean Patent Application Publication No. 2000-23031	04/25/2000	Korea			NO

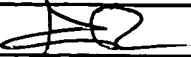
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

Examiner	Date Considered 4-5-05
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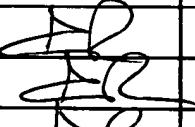
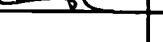
INFORMATION DISCLOSURE CITATION

Atty. Docket No.	04329.2802-01	Appln. No.	n/a
Applicant	Mari INOUE		
Filing Date	November 3, 2003	Group:	n/a

U.S. PATENT DOCUMENTS

Examiner Initials	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
	4,499,595	02-1985	Masaitis et al.	_____	_____	

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	2000-75467	3/14/00	Japan	_____	_____	Abstract
	2000-20564	01/21/00	Japan	_____	_____	Abstract
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Applicant	Mari INOUE		
Filing Date	November 3, 2003	Group:	n/a

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